

IN THE CLAIMS:

Please cancel originally-filed claims 1-37, and cancel substitute claims 1-22 filed in the underlying International Application PCT/EP2005/00041 under PCT Article 34, without prejudice. Please add new claims 38-58 as provided below. The listing and status of these claims are provided as follows, on separate sheets:

Claims 1-37 (Cancelled).

38. (New) A high-frequency atomizing device, comprising:

an atomizing arrangement configured to provide a spray mist jet and comprising a horn-shaped resonance body that is excitable to generate high-frequency vibrations;

a housing comprising at least one opening, wherein the particular housing is configured to enclose at least one portion of the atomizing arrangement and wherein the resonance body is provided proximate to the at least one opening;

a nozzle connected to the at least one opening;

a controllable gas supply arrangement configured to provide a flow of a gas to the housing;

a substrate holder arrangement configured to maintain a substrate in a particular position; and

at least one drying arrangement configured to at least one of dry or cure a spray mist coating applied to the substrate.

39. (New) The device of claim 38, wherein the atomizing arrangement is movable relative to the substrate.

40. (New) The device of claim 38, further comprising a storage tank configured to maintain a coating fluid.

41. (New) The device of claim 40, further comprising at least one particular temperature setting arrangement configured to affect a temperature of the coating fluid.

42. (New) The device of claim 41, wherein the at least one particular temperature setting arrangement is configured to be in a thermal communication with the storage tank.

43. (New) The device of claim 41, wherein the at least one particular temperature setting arrangement is configured to be in a thermal communication with the atomizing arrangement.

44. (New) The device of claim 38, further comprising at least one electric field arrangement configured to generate an electrical field in a region between the atomizing arrangement and at least one portion of the substrate holder.

45. (New) The device of claim 38, further comprising at least one magnetic field arrangement configured to generate a magnetic field in a region between the atomizing arrangement and at least one portion of the substrate holder.

46. (New) The device of claim 38, further comprising at least one temperature setting arrangement configured to affect a temperature of the gas.

47. (New) The device of claim 46, wherein the at least one temperature setting arrangement is configured to be in a thermal communication with the controllable gas supply arrangement.

48. (New) The device of claim 38, wherein the nozzle is configured to pass a gas therethrough so as to affect a dispersal of the spray mist jet.

49. (New) The device of claim 38, wherein the substrate holder arrangement is capable of positioning the substrate within the spray mist jet.

50. (New) The device of claim 49, wherein the substrate holder arrangement is capable of moving the substrate using six different degrees of freedom of movement.

51. (New) The device of claim 38, wherein the at least one drying arrangement comprises a heat source.

52. (New) The device of claim 51, wherein the at least one drying arrangement further comprises a heating housing that includes at least one heating opening which is open on one side thereof, and wherein the heating housing is in a communication with the controllable gas supply arrangement, and configured to provide a flow of a heated gas therethrough.

53. (New) The device of claim 51, wherein the heat source comprises an infrared source.

54. (New) The device of claim 38, further comprising a controllable suction arrangement configured to at least one of influence a dispersal of the spray mist jet or withdraw at least one portion of the spray mist jet.

55. (New) The device of claim 54, further comprising at least one further housing that at least partially surrounds at least one of the atomizing arrangement, the substrate holder arrangement, or the controllable suction arrangement.

56. (New) The device of claim 55, wherein the at least one further housing at least partially surrounds the at least one drying arrangement.

57. (New) The device of claim 38, further comprising a processing arrangement configured to control at least one of the atomizing arrangement, the substrate holder arrangement, the controllable gas supply arrangement or the at least one drying arrangement.

58. (New) The device of claim 55, wherein the at least one further housing has a form of a coating chamber, and wherein the atomizing arrangement comprises at least one further temperature setting arrangement configured to affect a temperature of the coating chamber.